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APPLICATION NO.		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/768,611		01/29/2004	Eiji Hasegawa	P/29-1647	7083
2352	7590	05/31/2006		EXAMINER	
		BER GERB & SOFI	TOLEDO, FERNANDO L		
1180 AVEN NEW YORI		THE AMERICAS 100368403		ART UNIT	PAPER NUMBER
	<b>,</b> - · - ·			2823	· · · · · · · · · · · · · · · · · · ·
				DATE MAILED: 05/31/200	6

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)						
Advisory Action	10/768,611	HASEGAWA, EIJI						
Before the Filing of an Appeal Brief	Examiner	Art Unit						
	Fernando L. Toledo	2823						
The MAILING DATE of this communication appe	ars on the cover sheet with the c	correspondence add	ress					
THE REPLY FILED <u>13 April 2006</u> FAILS TO PLACE THIS APF	PLICATION IN CONDITION FOR A	LLOWANCE.						
<ol> <li>The reply was filed after a final rejection, but prior to or o this application, applicant must timely file one of the follo places the application in condition for allowance; (2) a No (3) a Request for Continued Examination (RCE) in comp following time periods:</li> </ol>	owing replies: (1) an amendment, a otice of Appeal (with appeal fee) in liance with 37 CFR 1.114. The repl	ffidavit, or other evide compliance with 37 (	ence, which CFR 41.31; or					
a) The period for reply expires 3 months from the mailing date of								
b) The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection.								
Examiner Note: If box 1 is checked, check either box (a) or (b)	ONLY CHECK BOX (b) WHEN THE FI		OWT NIHTIW D					
MONTHS OF THE FINAL REJECTION. See MPEP 706.07(f Extensions of time may be obtained under 37 CFR 1.136(a). The date on		) and the appropriate exte	ension fee have					
been filed is the date for purposes of determining the period of extension a CFR 1.17(a) is calculated from: (1) the expiration date of the shortened sta above, if checked. Any reply received by the Office later than three month earned patent term adjustment. See 37 CFR 1.704(b).	and the corresponding amount of the fee. atutory period for reply originally set in the	The appropriate extension final Office action; or (2)	on fee under 37 as set forth in (b)					
NOTICE OF APPEAL  2. The Notice of Appeal was filed on A brief in com	pliance with 37 CEP 41 37 must be	a filed within two mon	the of the date					
2. The Notice of Appeal was filed on A brief in compliance with 37 CFR 41.37 must be filed within two months of the date of filing the Notice of Appeal (37 CFR 41.37(a)), or any extension thereof (37 CFR 41.37(e)), to avoid dismissal of the appeal. Since a Notice of Appeal has been filed, any reply must be filed within the time period set forth in 37 CFR 41.37(a).								
AMENDMENTS			/·					
3. The proposed amendment(s) filed after a final rejection,  (a) They raise new issues that would require further co	nsideration and/or search (see NO		because					
(b) ☐ They raise the issue of new matter (see NOTE belo (c) ☐ They are not deemed to place the application in be		educing or simplifying	the issues for					
appeal; and/or (d)☐ They present additional claims without canceling a	corresponding number of finally re	jected claims.						
NOTE: (See 37 CFR 1.116 and 41.33(a)).	· ·	•						
4. The amendments are not in compliance with 37 CFR 1.1		ompliant Amendment	(PTOL-324).					
5. 🔲 Applicant's reply has overcome the following rejection(s								
<ol> <li>Newly proposed or amended claim(s) would be a the non-allowable claim(s).</li> </ol>	Ilowable if submitted in a separate	, timely filed amendm	nent canceling					
7.  For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is pro The status of the claim(s) is (or will be) as follows:		ill be entered and an	explanation of					
Claim(s) allowed: Claim(s) objected to:								
Claim(s) objected to: Claim(s) rejected:								
Claim(s) withdrawn from consideration:								
AFFIDAVIT OR OTHER EVIDENCE								
<ol> <li>The affidavit or other evidence filed after a final action, b because applicant failed to provide a showing of good ar</li> </ol>								

- and was not earlier presented. See 37 CFR 1.116(e).
- 9. The affidavit or other evidence filed after the date of filing a Notice of Appeal, but prior to the date of filing a brief, will not be entered because the affidavit or other evidence failed to overcome all rejections under appeal and/or appellant fails to provide a showing a good and sufficient reasons why it is necessary and was not earlier presented. See 37 CFR 41.33(d)(1).
- 10. The affidavit or other evidence is entered. An explanation of the status of the claims after entry is below or attached.

## REQUEST FOR RECONSIDERATION/OTHER

11. A The request for reconsideration has been considered but does NOT place the application in condition for allowance because: See Continuation Sheet.

12. Note the attached Information Disclosure Statement(s). (PTO/SB/08 or PTO-1449) Paper No(s).

13. Other: \_\_\_

Fernando L. Toledo Patent Examiner Art Unit 2823

Continuation of 11. does NOT place the application in condition for allowance because: Regarding claim 1, Applicant contests that Wolf merely discusses the process temperature for doped-impurities and that Wolf teaches a range for RTP to be from 420-1150C. Examiner respectfully submits that Wolf discloses that many process that are carried out at above 900C causes unwanted diffusion (it would be advantageous to avoid unwanted diffusion). On the other side, it is Hu that establishes an RTP for oxidation at 1100C and not Wolf and thus it, according to Wolf, be the highest temperature of the semiconductor-making process. Regarding claims 13 and 21, Hu's figure 6 describes the same process as that of Applicant. The percentage of nitrogen would decrease in an exponential manner as it goes deeper into the oxide, however, the concentration of nitrogen would decrease in a constant manner.